



New trends in semiconductor detectors

Shaun Roe, CERN

S. Roe, Erice 28 September-4 October 2003



New trends

- Recent History
- Review of the problem
- Silicon
 - Novel geometries: MAPS, 3D, Defect engineering: Cold, Oxygenated
- 'New' materials
 - Diamond, amorphous silicon, Silicon carbide
- Other ideas...
 - Depfet, new pixel layout



Potted history

- Rewind twelve years (pre-web!):
 - Silicon detectors operated to 100V
 - Irradiations to 10^{13} neutrons/cm² started, didn't look promising
 - Some LEP detectors showing radiation damage
 - Double sided detectors looked good (?)
 - Analogue electronics, water cooling, copper power and readout, OS9, PAW, FORTRAN, dial&read detector testing...



Recent history

- Last ten years of HEP investigations for LHC
 - Ordinary photodiodes investigated in neutron, proton and gamma sources reveals initially that the leakage current increases but anneals. Increase in operating voltage also seen, and capacitance effects. (RD2, RD20)
 - Increase in operating voltage seen to further increase after irradiation, and be very temperature dependent. (UCSC, RD20, RD2). Model proposed by Lindstrom, Fretwurst.
 - First projections of the model to LHC scenario show the detectors are unworkable unless kept cold, and even then there is a danger. Principle problem identified as the depletion voltage.
 - All subsequent improvements to LHC detectors have concentrated on the depletion voltage problem.

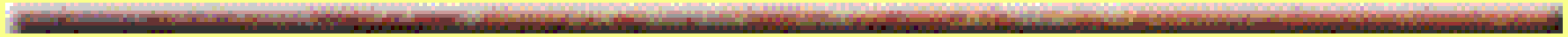


Today's snapshot

- Detectors far more robust, but cooled
 - Operate routinely to 500V
 - Evaporative or refrigerant cooling
 - Routine irradiations to $>3 \times 10^{14}$ n/cm²
- Systems evolution
 - Optical readout
 - Cables, hybrids more adventurous
 - Testing with LabView, Linux, C++, NI-VXI or PCI (USB soon?), logic in FPGAs...



A modern module

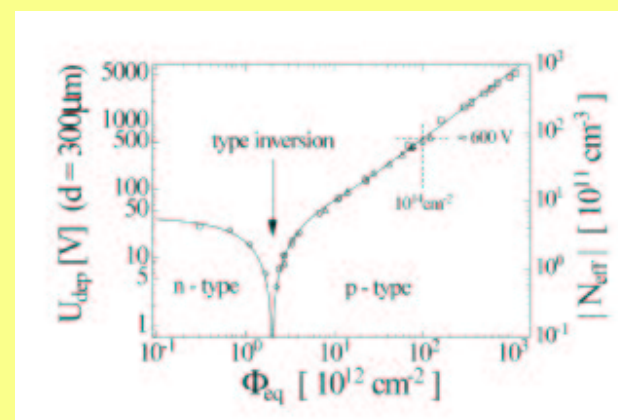
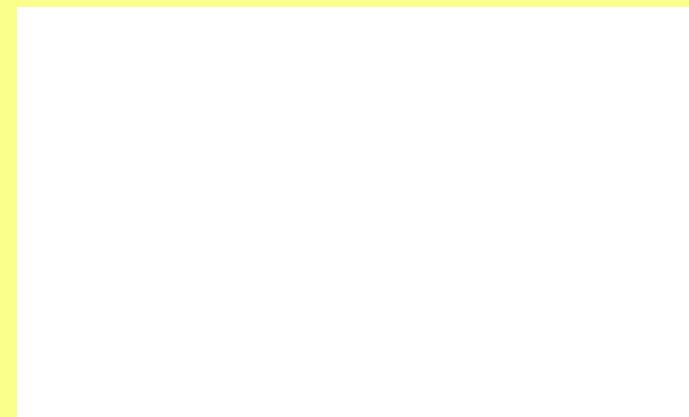


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Review of radiation problems (1)

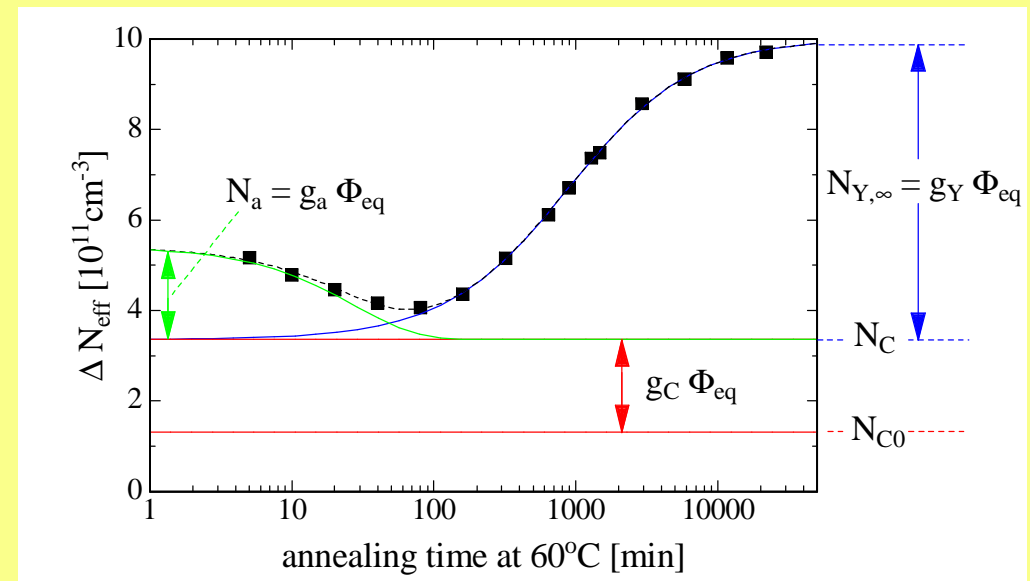
- Most obvious: Leakage current, giving rise to noise
 - Not such a problem at small shaping times
 - 3.99×10^{-17} A/cm (1MeV n)
- 'LHC era' problem of depletion voltage rising beyond operable limits





Review of radiation problems(2)

- 'Reverse annealing'
 - Depletion voltage continues to change after irradiation
 - Strongly temperature dependent
- 'Hamburg model'



Michael Moll, CERN

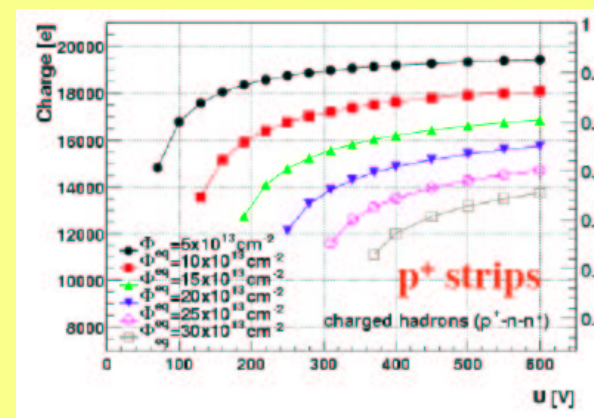
$$\Delta N_{\text{eff}}(\Phi_{\text{eq}}, t) = N_a(\Phi_{\text{eq}}, t) + N_C(\Phi_{\text{eq}}, t) + N_Y(\Phi_{\text{eq}}, t)$$

= **beneficial annealing** + **stable damage** + **reverse annealing**

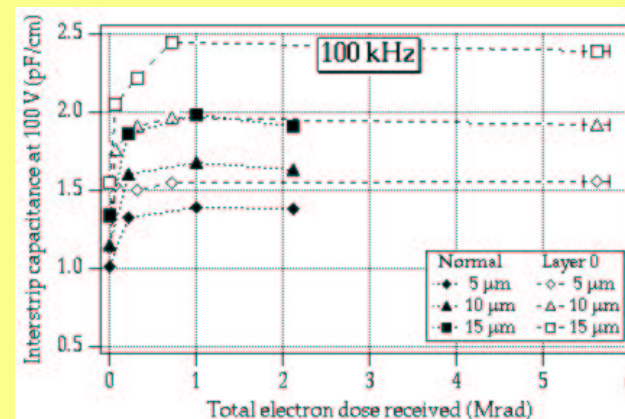


Review of radiation problems(3)

- Trapping: some charge simply 'disappears'
- Secondary effects: increase in capacitance



Gregor
Kramberger,
Ljubljana



Richard
Wheadon, RD20



Looking forward

- New colliders may be ten times the luminosity of LHC
 - Principle challenge (for an SCT) is in the sensors
 - Depletion voltage remains a problem
 - Trapping becomes more significant
- Different approaches adopted
 - Geometrical: reduce the collection/depletion distance so a lower voltage can be used
 - Material: treat the silicon or use a different material to reduce radiation damage

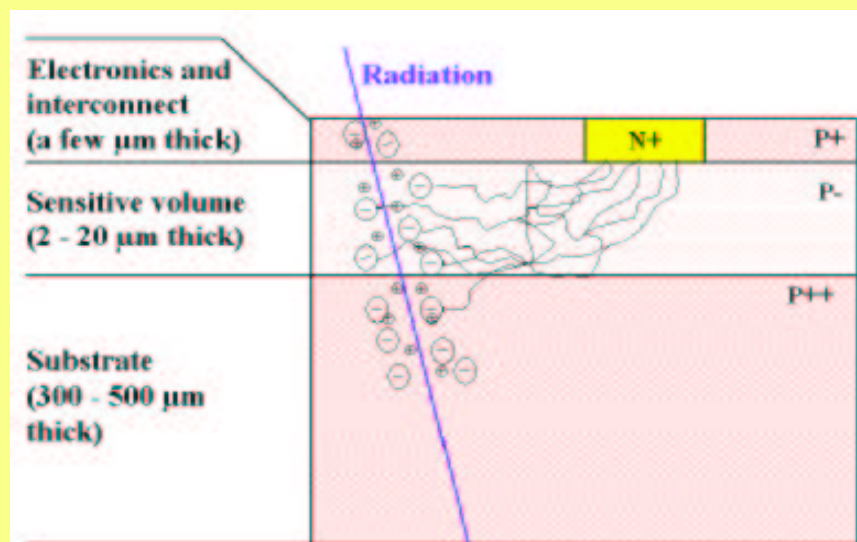


MAPS: Monolithic active pixel sensors

- Sensitive detector layer is manufactured with the electronics

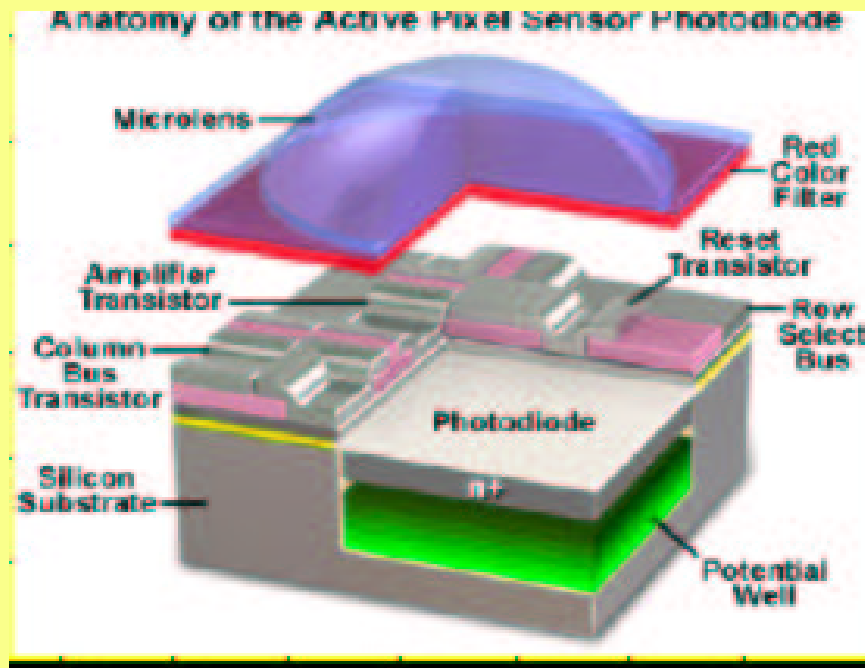
Active Pixel Sensor technologies have been around since 1993 for commercial application
Specific designs required for HEP application (1999)

Groups: Strasbourg, RAL (thanks: Renato Turchetta)



NIM A458(2001) 677-689

MAPS tests



First prototype: 512x512



MAPS design for HEP/space

- Specific design necessary:

- To increase active area ratio
- Low noise, high dynamic range, faster
- Thin sensors for reduced material
- Sensors should be larger than the reticle
- Radiation resistance

already achieved

specific CMOS design

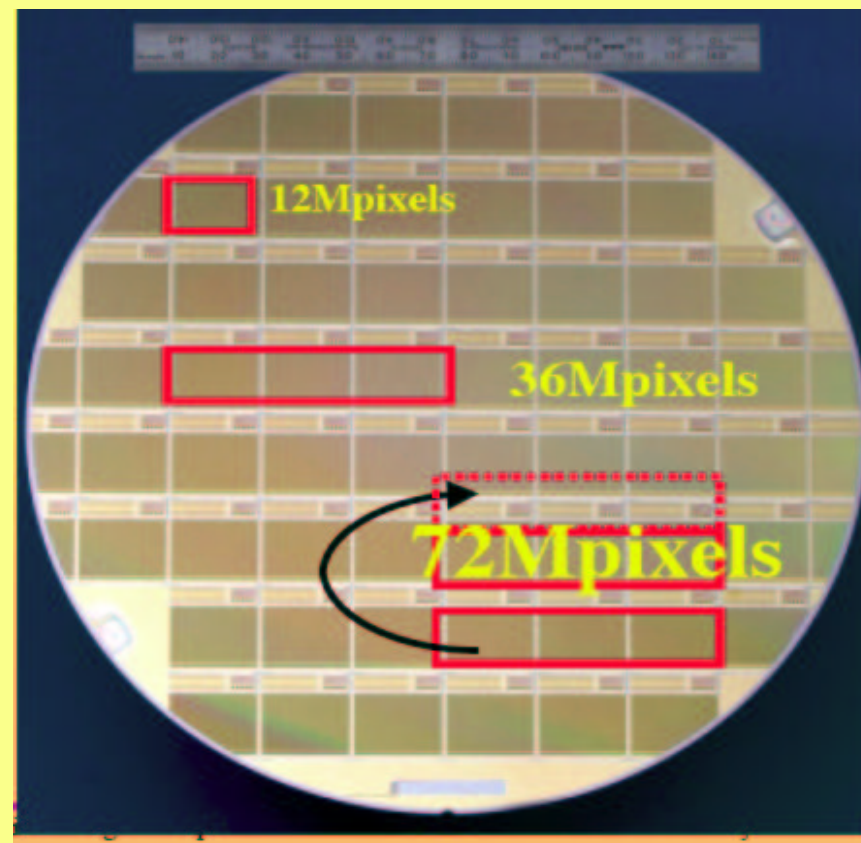
Backthinning to $50\mu\text{m}$ achieved

Stitching or clever dicing investigated

Apply bias to epitaxial layer

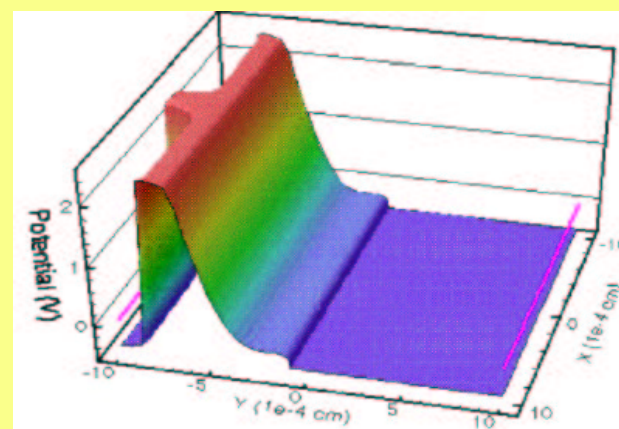
MAPS beam tests

- 99.5% efficiency
- S/N of 40 ($20\mu\text{m}$ thick epitaxy)
- $1.5\mu\text{m}$ resolution on $20\mu\text{m}$ pitch
- Deterioration seen at 6kGy , 10^{11}p/cm^2



MAPS for the future

- Radiation hardness needs to be addressed
 - Present design uses diffusion so is slow and prone to carrier lifetime degradation (trapping)
 - Applying a detector bias should be possible to speed collection and minimize trapping



potential

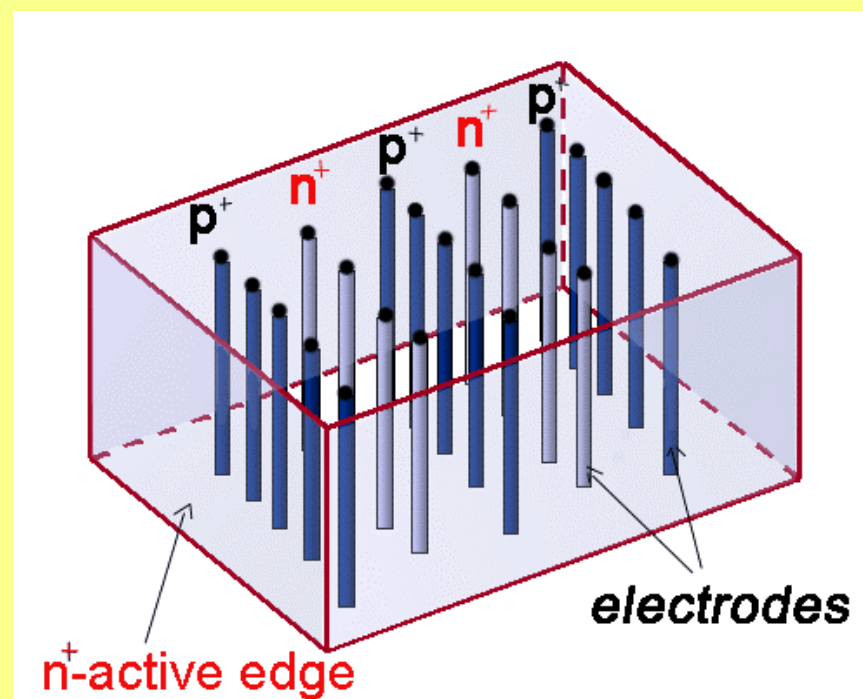
Biasing
structure



'3D' detectors

- Using MEMS (micro electro mechanical systems) techniques, vertical junctions are made (MBC, Brunel, Hawaii)

- ❖ NIMA 395 (1997) 328
- ❖ IEEE Trans Nucl Sci 46 4 (1999) 1224
- ❖ IEEE Trans Nucl Sci 48 2 (2001) 189
- ❖ IEEE Trans Nucl Sci 48 6 (2001) 2405
- ❖ IEEE Trans Nucl Sci 48 5 (2001) 1629
- ❖ CERN Courier, Vol 43, Number 1, Jan 2003



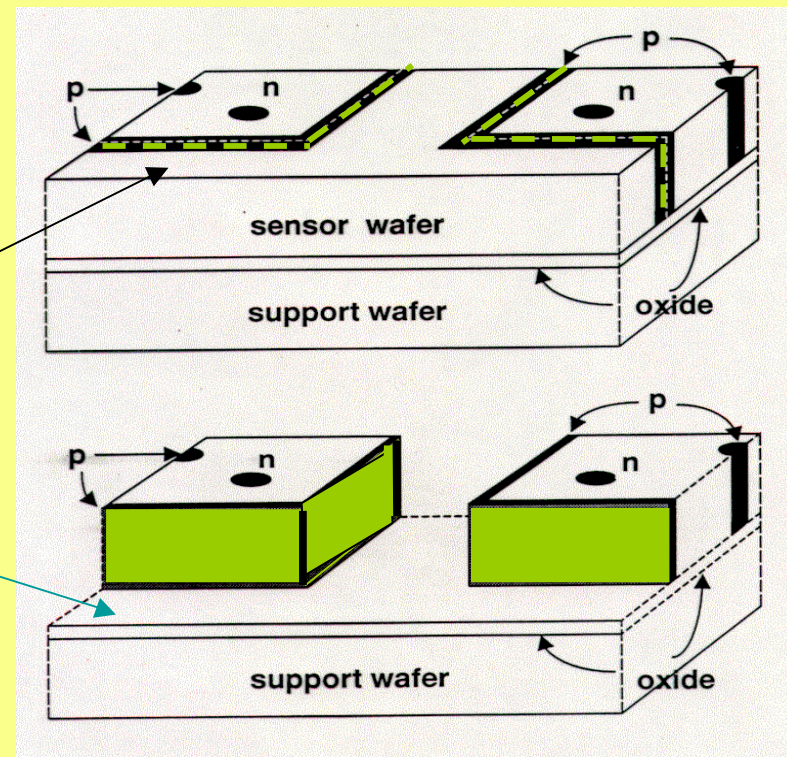
With thanks to: Cinzia daVia

3D-processing

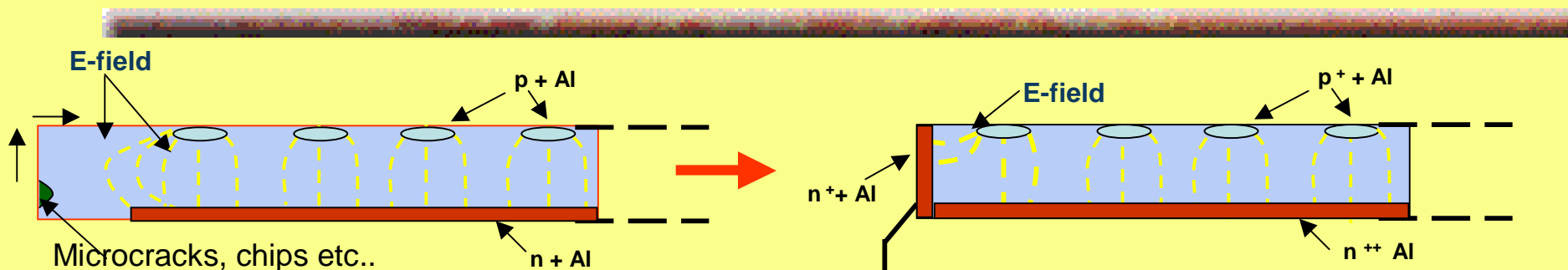
- Undergoing tests for TOTEM: edgeless operation is important

A trench is etched and doped to make a contact

After the first steps, the material around the detectors is etched away and the support removed: no sawing is required



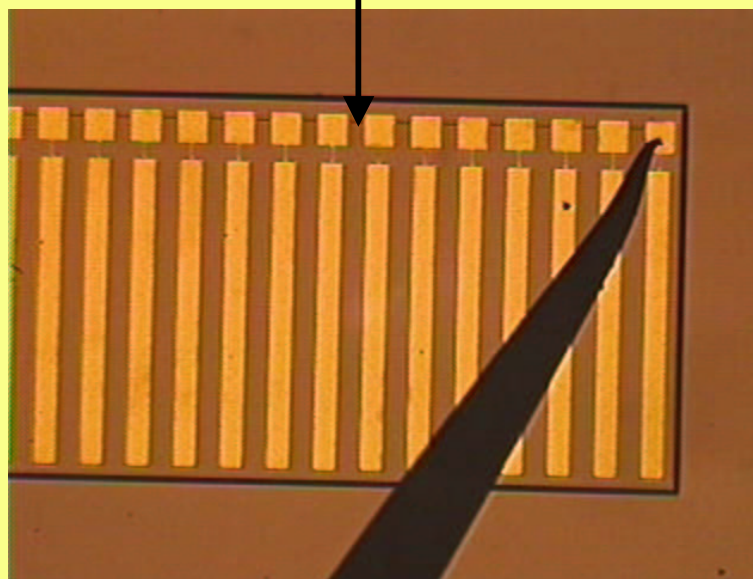
3D: 'Edgeless' detectors



GUARD RING
Sinks surface leakage current

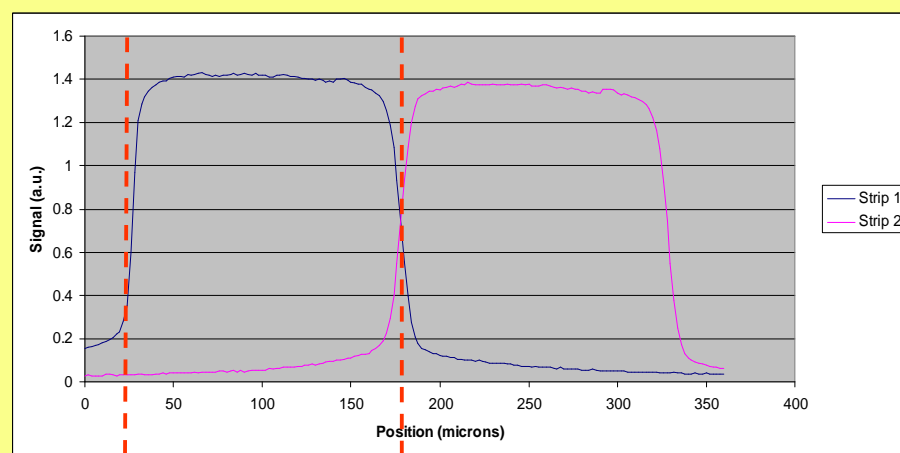
Planar 3D
Sinks surface leakage current

- ❖ 30 μm pitch strips
- ❖ 240 μm thick
- ❖ n-type silicon
- ❖ $\rho = 10 \text{ k}\Omega\text{cm}$
- ❖ 3 x 4 mm^2

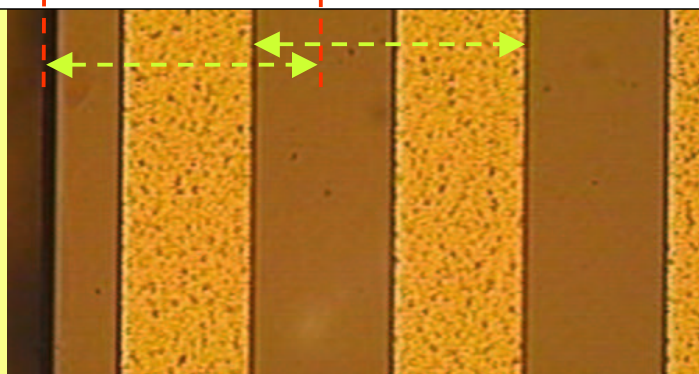




3D: 'Edgeless' detectors



- X ray microbeam scanned across the detector
- Measured 'dead' region is only $5\mu\text{m}$ at the edge of the detector

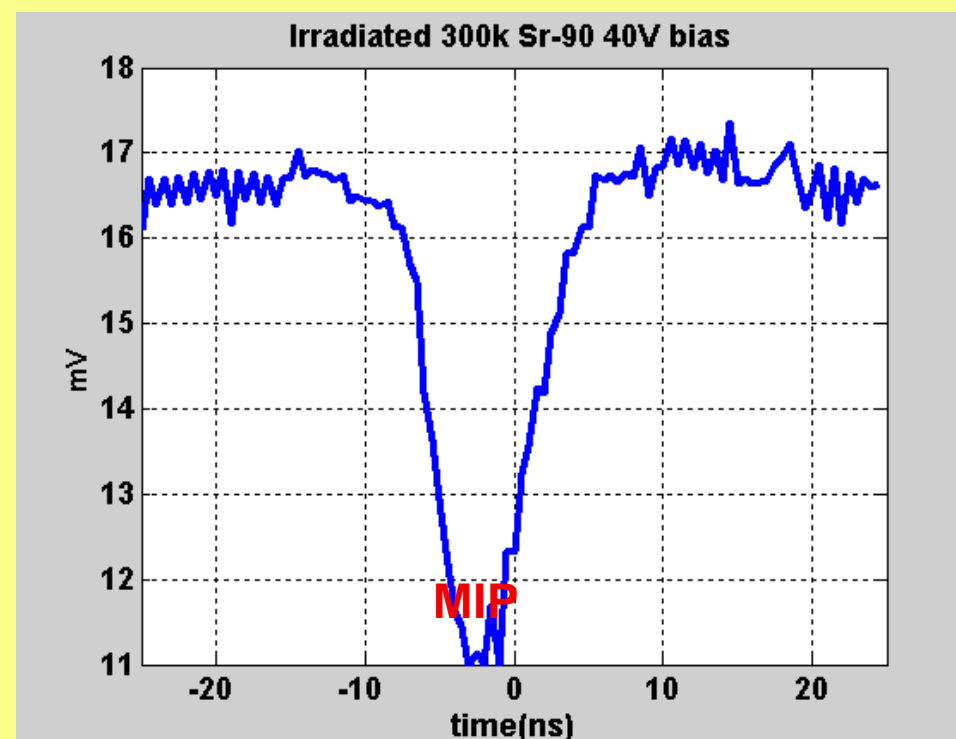


20 Volts Bias



3D: Radiation hardness

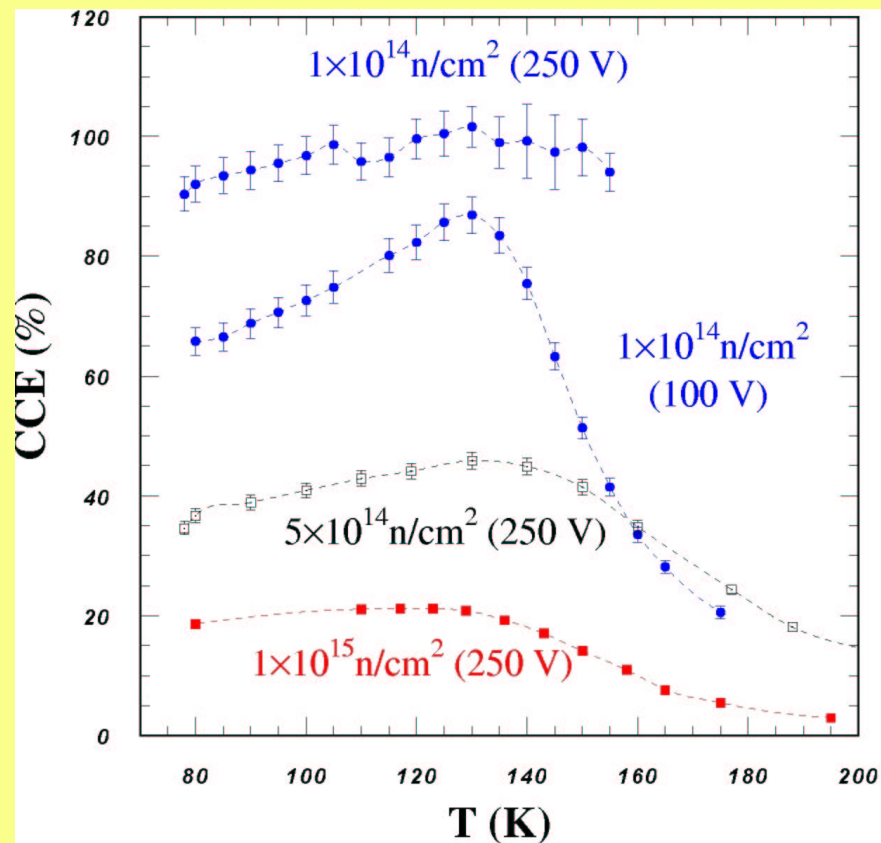
- Irradiated to 10^{15} p/cm²
 - Bias voltage 40V (max beneficial annealing)
 - Risetime 3.5ns, <10ns width
 - CCE 60%
 - Irradiated, stored, measured at 20°C
- Results also exist for 2×10^{15} p/cm²
 - Different storage conditions





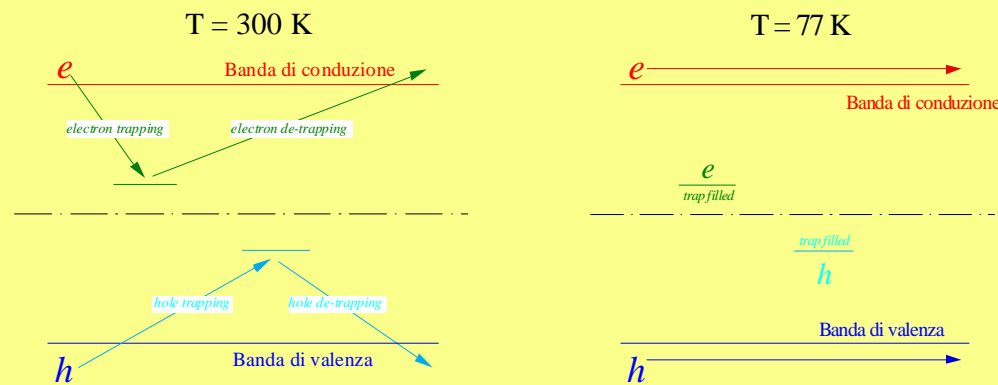
Cold Silicon

- Relies on freezing of the contributing traps
 - Requires 140K or below
 - Addresses both operating voltage and charge trapping problem





Cold silicon: Lazarus effect

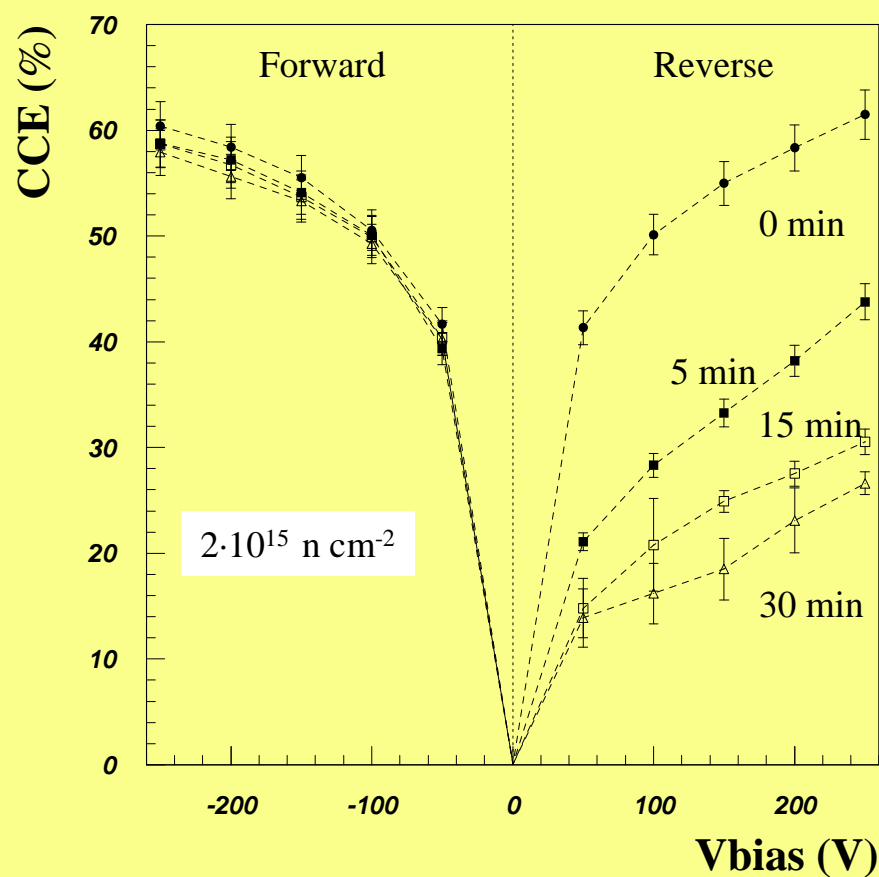


$$CCE \propto \left(\frac{d}{D}\right)^2 \exp\left(-\frac{t_{drift}}{\tau_{trap}}\right)$$

- Trap emission time becomes very long
 - Traps fill up and no longer contribute to electrical behaviour



Cold silicon



- Both forward and reverse biasing is possible
- Edgeless operation is being investigated

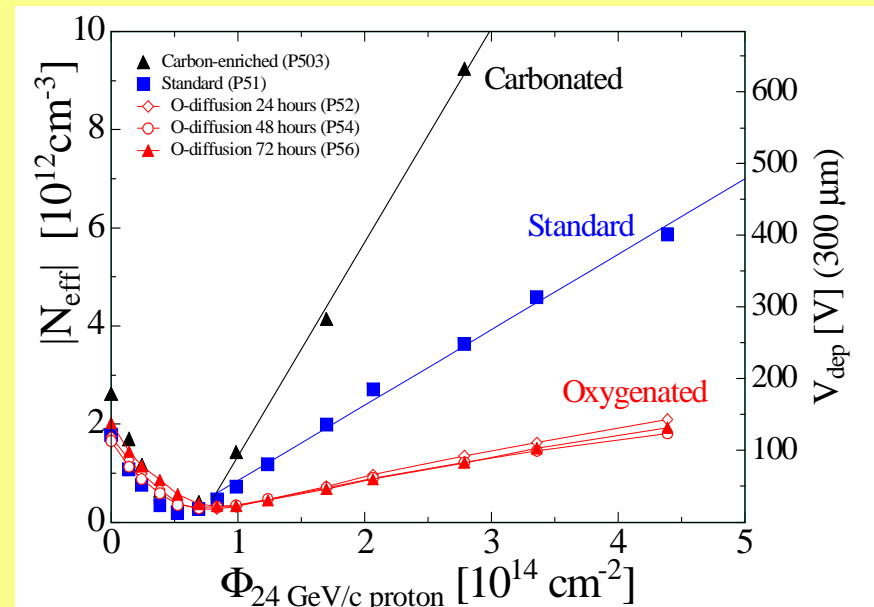
Cut edge at
0, strips
25 μ m

QuickTime™ and a TIFF (LZW) decompressor are needed to see this picture.



Oxygenated silicon

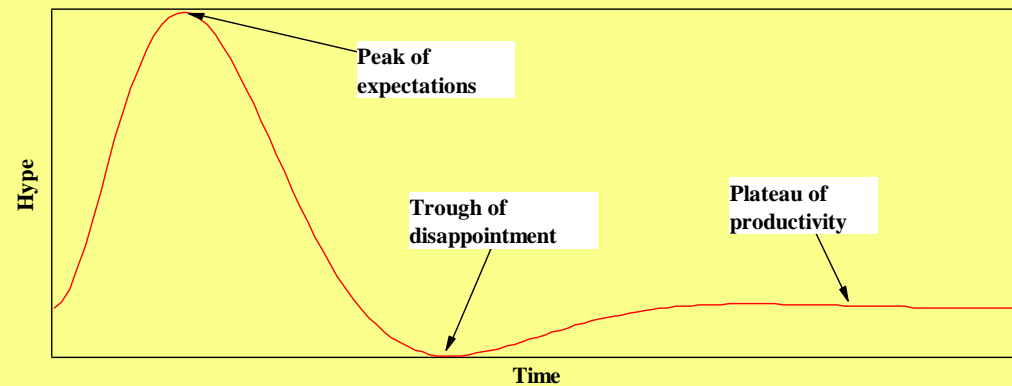
- Defect kinetics approach
 - Attempts to understand the microscopic causes of radiation damage
 - First studies implicated oxygen and carbon in the defect creation process
 - Diffusion oxygenated float zone silicon (DOFZ) investigated



Thanks to: Michael Moll



New materials

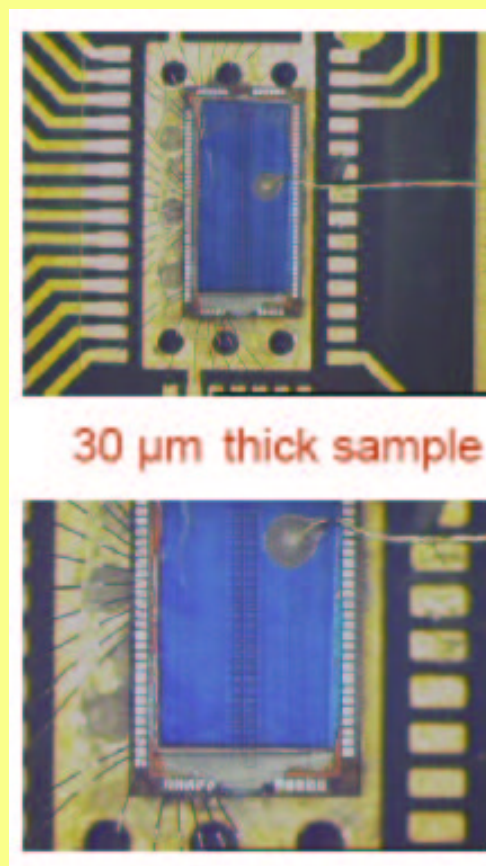


- 'New material syndrome'

- Other materials not as commercially important as silicon, tend to be technologically less mature
- Typical problems are trapping and obtaining uniform material (and money)

Amorphous silicon

- Hydrogenated amorphous silicon
 - Initial work (1985-1995) produced only small signals
 - MAPS approach now being tried
 - Layers of 10-30 μm can be deposited
 - Aim is to fully deplete and achieve charge transition of 10ns or less



Thanks To: Pierre Jarron



Amorphous silicon: technology

- Plasma Enhanced Chemical Vapour Deposition (PECVD)
 - Low temperature (220°C)
 - 6 hours for a 30 μ m layer
 - Silane decomposition





Amorphous silicon: properties

- c-Si

Density [g/cm³]

2.3

Hole mobility [cm²/Vs]

1350

Electron mobility [cm²/Vs]

480

Bandgap [eV]

1.12

W [eV]

3.6

- A-Si:H

2.25

2-5

0.005

1.7-1.8

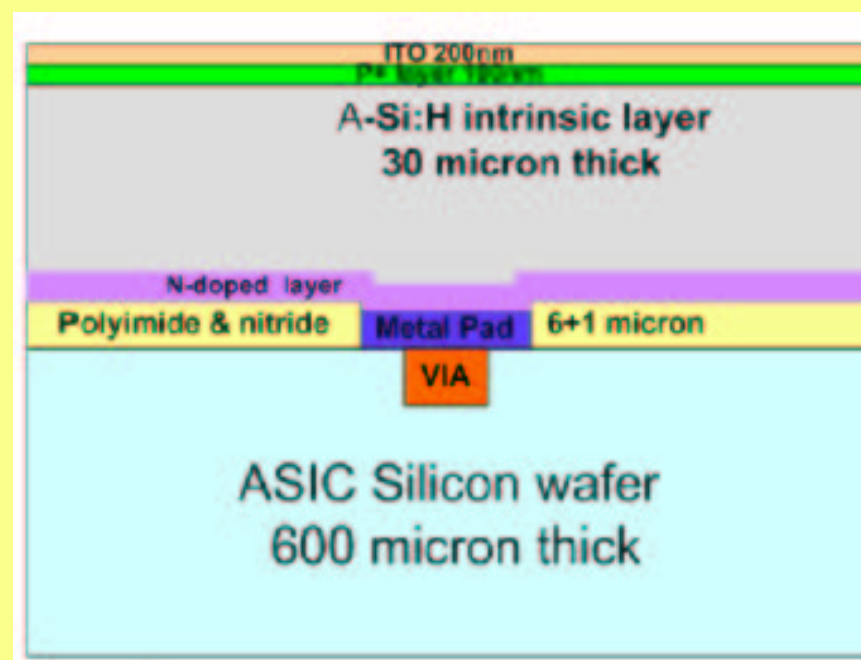
4-4.8

- Band structure is complex
- Defect density is $\sim 10^{15}/\text{cm}^3$, charge lifetime depends strongly on this
- Trapping sites (incl. Radiation produced) are compensated by highly mobile H



Amorphous silicon: devices

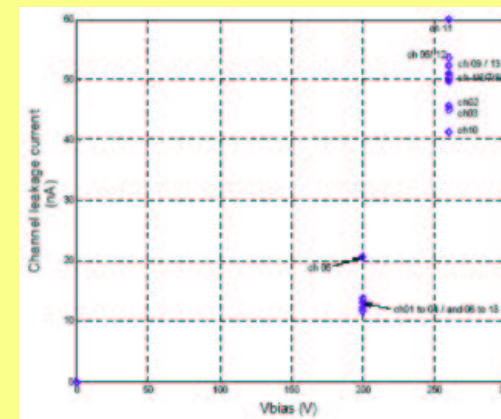
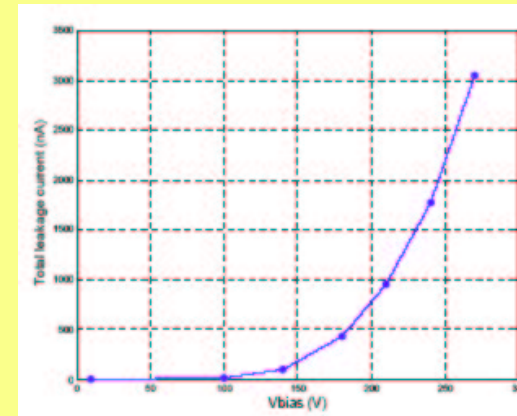
- **Multilayer composition**
 - Bottom thin n-doped layer (20nm)
 - Middle thick i-layer (5-30 μ m)
 - Top thin p-doped layer (40nm)
 - Indium Tin Oxide (100nm)
 - 13 μ m and 30 μ m thick layer devices have been made with 94 x 68 μ m pixels





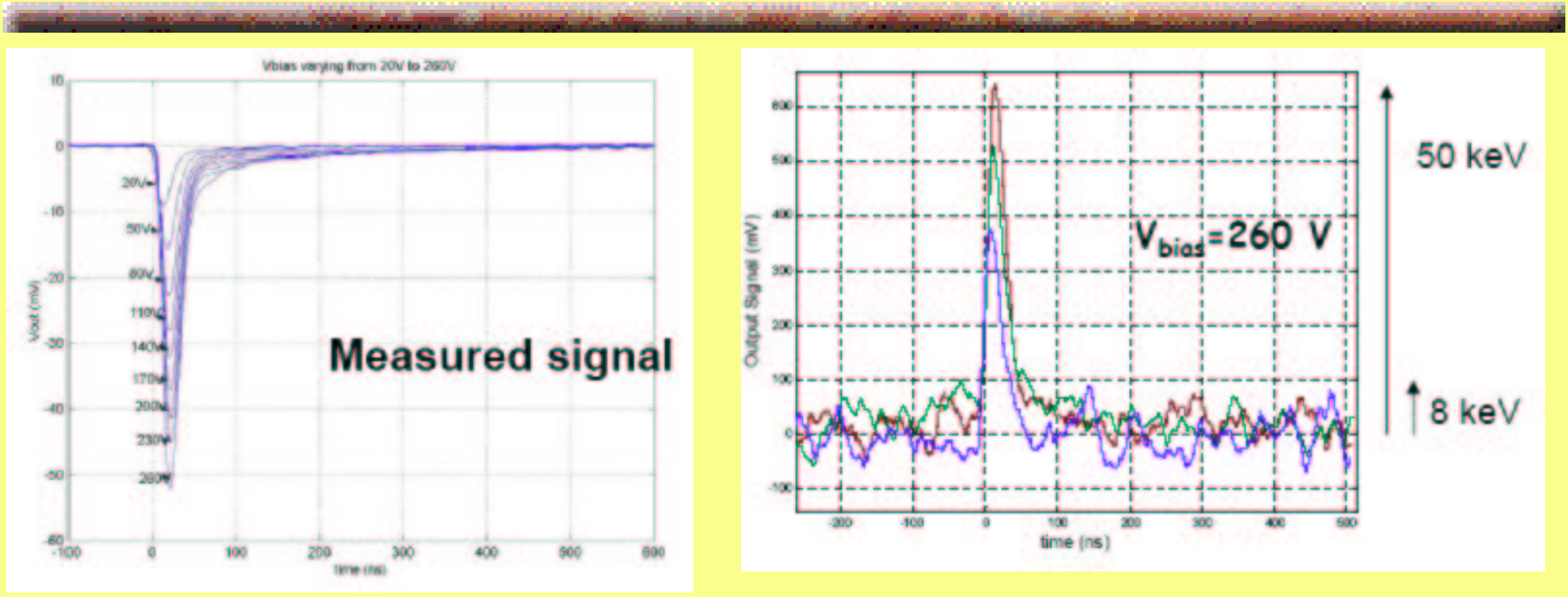
Amorphous Silicon: DC characteristic

- Leakage current
 - Pixel leakage 10nA at 200V, 40nA at 250V
 - 'soft' breakdown characteristic
- Depletion
 - Full depletion ~400V for 30 μ m





Amorphous silicon: signal response

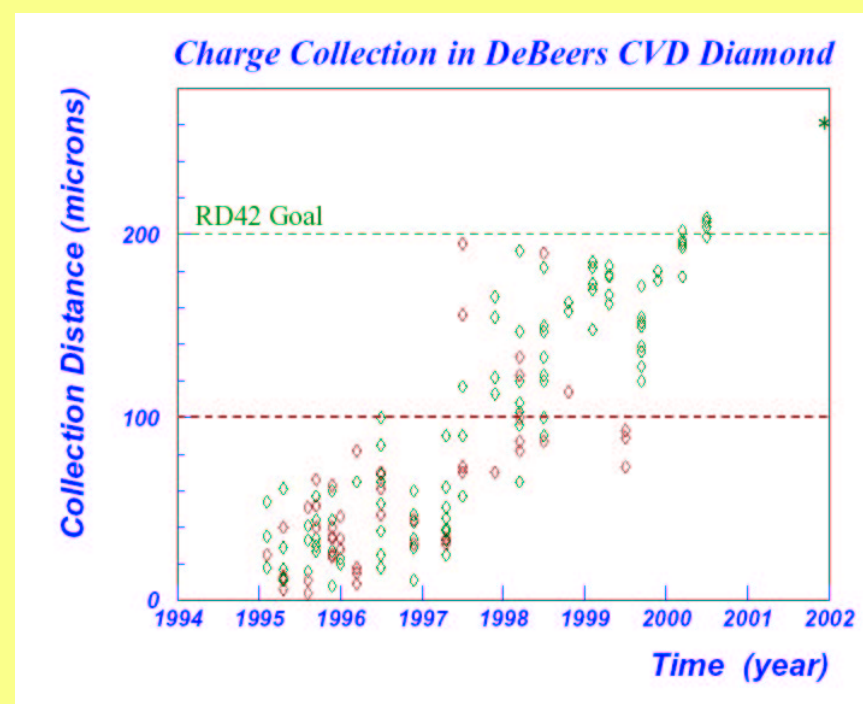


- Results shown for 30 μ m thick layer
 - Signal of 2400 e⁻/30 μ m (not fully depleted!)



Diamond

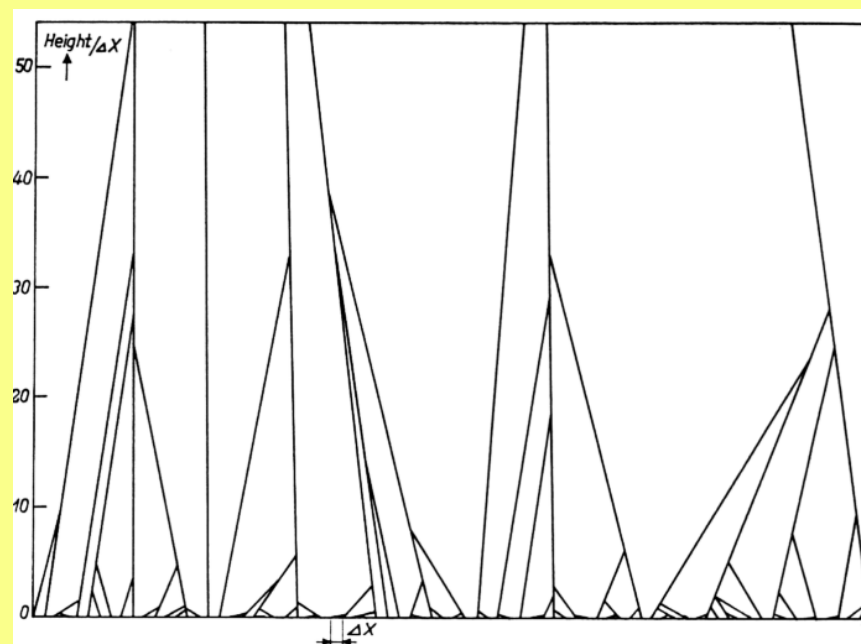
- RD42 leads the way..
 - Working with Element Six to improve properties
 - Polycrystalline silicon characterized in terms of 'collection distance' (measure of charge lifetime/trapping)
 - 5" wafers possible



Thanks to: Alexander Oh

Diamond properties

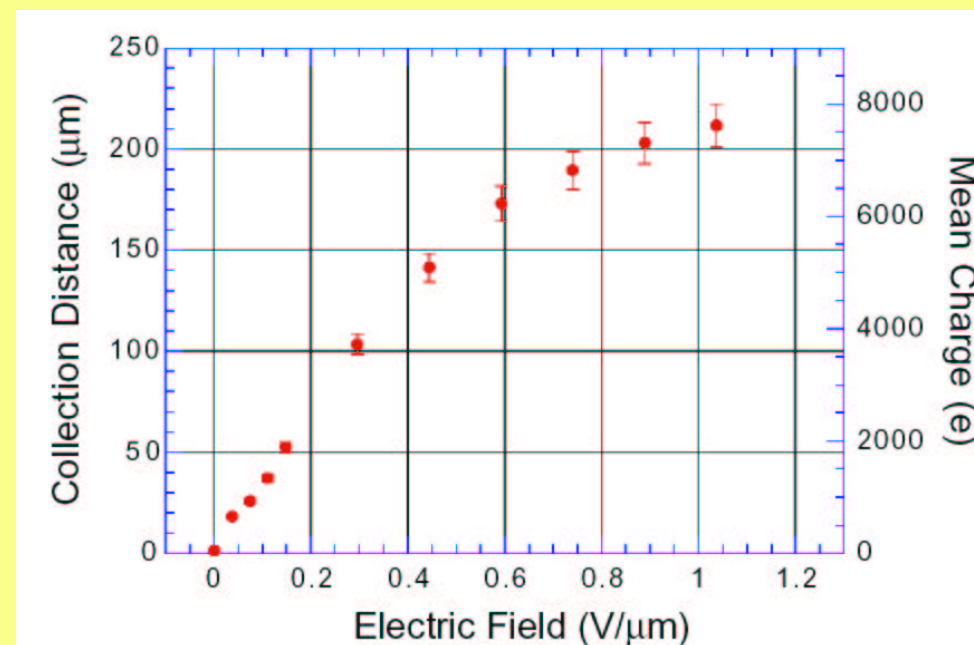
- Polycrystalline diamond
 - Produced by CVD
 - Bandgap 5.47
 - Ionization energy 13eV
 - Smaller signal
 - Better radiation performance
 - Low leakage current
 - High mobility
 - Charge collection < 100%
- MIP signal 1.9 smaller than Si for same X_0





Diamond properties

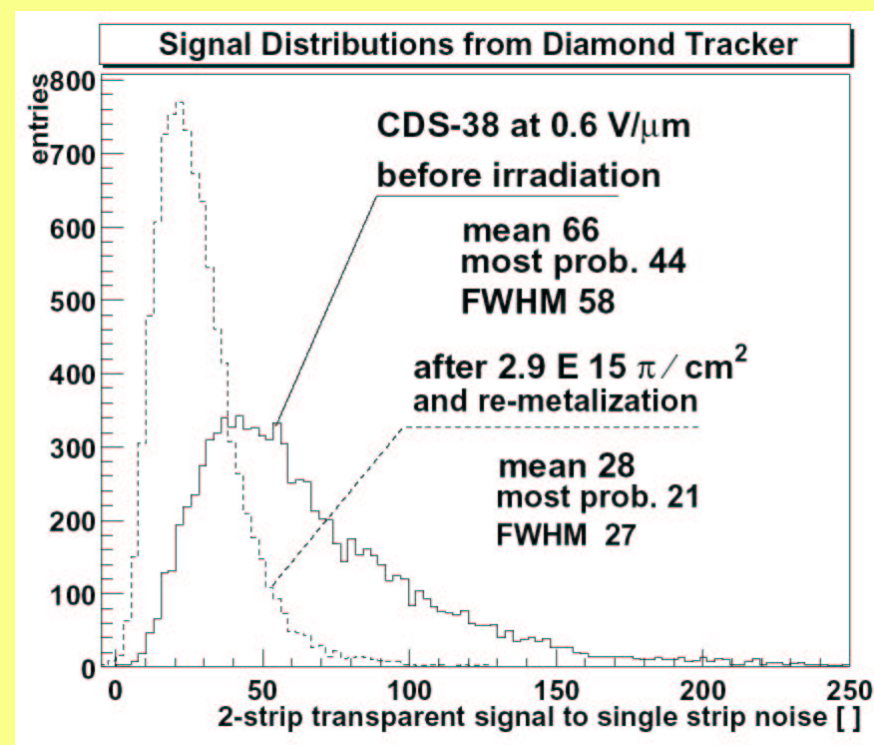
- Sensitive to metallization process
 - E.g Cr/Au, Ti/Au, Ti/W...
- For full collection need $\sim 1\text{V}/\mu\text{m}$
 - Polycrystalline structure still influences resolution (lateral field)





Diamond: radiation hardness

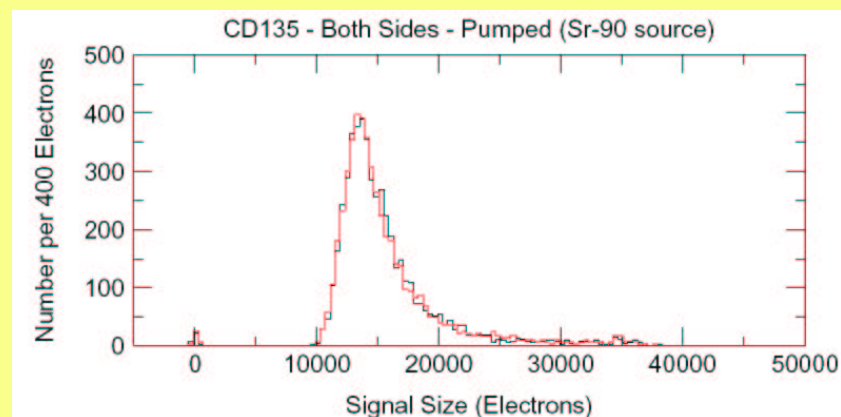
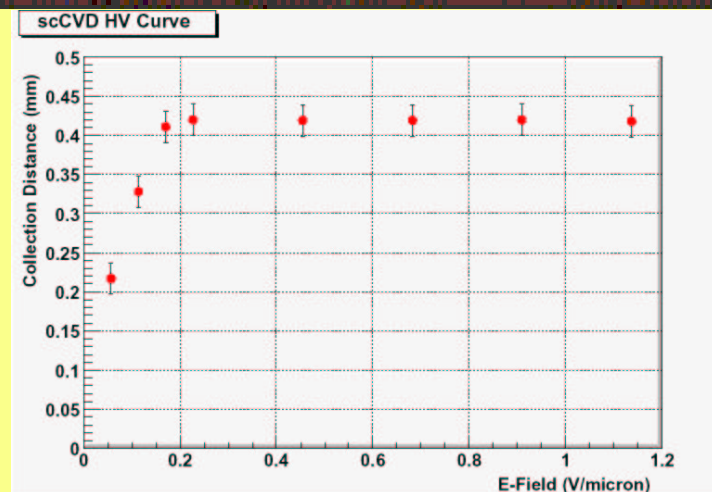
- Studied with various particles
 - More rad-hard to charged hadrons than neutrons
 - Survives 2.9×10^{15} /cm² pions
 - This gives 50% of charge





New: monocrystalline diamond

- Less defects
 - No grain boundary problem
 - Collection saturates at $0.2\text{V}/\mu\text{m}$
 - 100% efficient



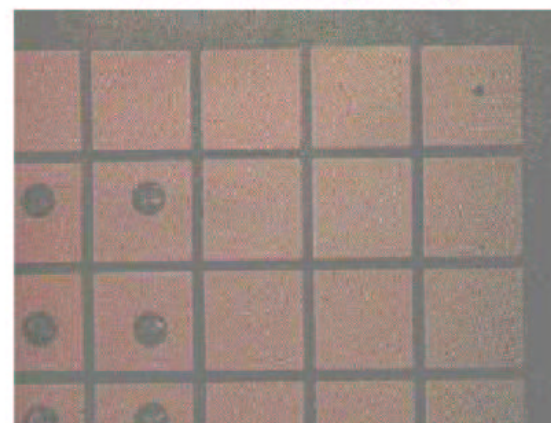
Diamond: pixel detectors

ATLAS FE/I Pixels (Al)



- ◆ Atlas pixel pitch $50\mu\text{m} \times 400\mu\text{m}$
- ◆ Over Metalisation: Al
- ◆ Lead-tin solder bumping at IZM in Berlin

CMS Pixels (Ti-W)



- ◆ CMS pixel pitch $125\mu\text{m} \times 125\mu\text{m}$
- ◆ Metalization: Ti/W
- ◆ Indium bumping at UC Davis

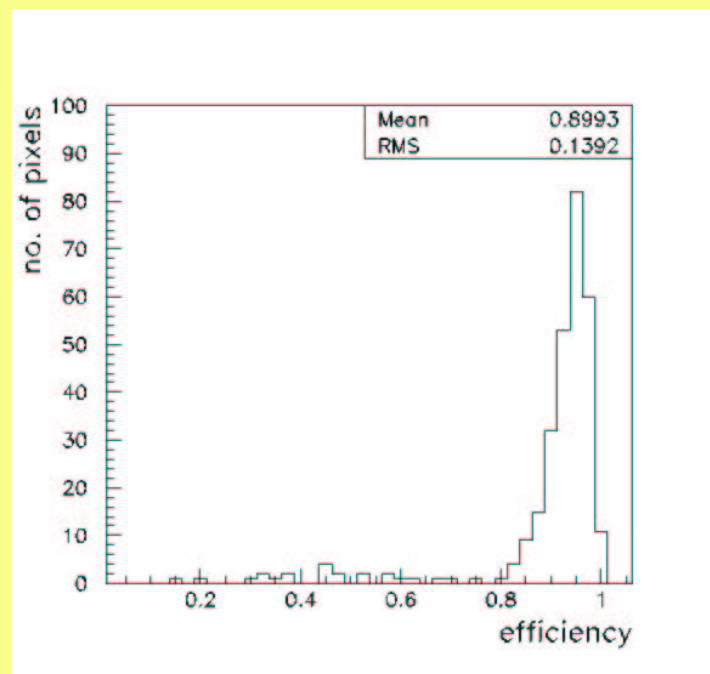
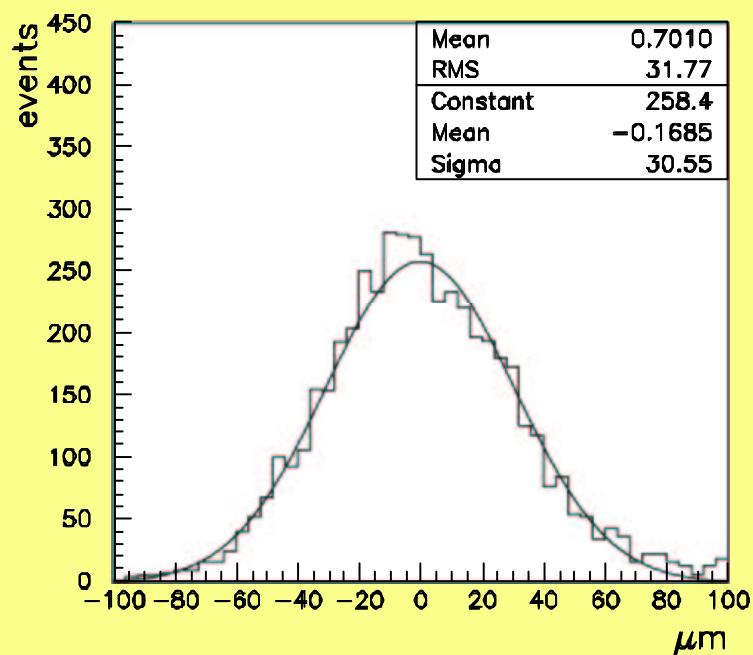
→ Bump bonding yield $\approx 100\%$ for both ATLAS and CMS devices

New radiation hard chips produced this year.

polycrystalline



Diamond detectors



- CMS results: $31\mu\text{m}$ resolution, 90% efficiency



Silicon Carbide

- Great promise
 - Greater displacement energy, should be radiation hard
 - More charge than diamond, less than silicon

Property	Diamond	4H SiC	Si
E_g [eV]	5.5	3.3	1.12
$E_{\text{breakdown}}$ [V/cm]	10^7	$4 \cdot 10^6$	$3 \cdot 10^5$
μ_e [cm^2/Vs]	1800	800	1450
μ_h [cm^2/Vs]	1200	115	450
v_{sat} [cm/s]	$2.2 \cdot 10^7$	$2 \cdot 10^7$	$0.8 \cdot 10^7$
Z	6	14/6	14
ϵ_r	5.7	9.7	11.9
e-h energy [eV]	13	8.4	3.6
τ_h [s]	10^{-9}	$5 \cdot 10^{-7}$	$2.5 \cdot 10^{-3}$
Wigner En.[eV]	43	25	13-20

Thanks to: Camilla Ronnqvist,
Michael Moll



Silicon Carbide

- Technology still immature
 - Defects seen in growth include step bunching, carrots and micropipes
 - Pipes may be mobile
 - Epitaxial is better, but expensive

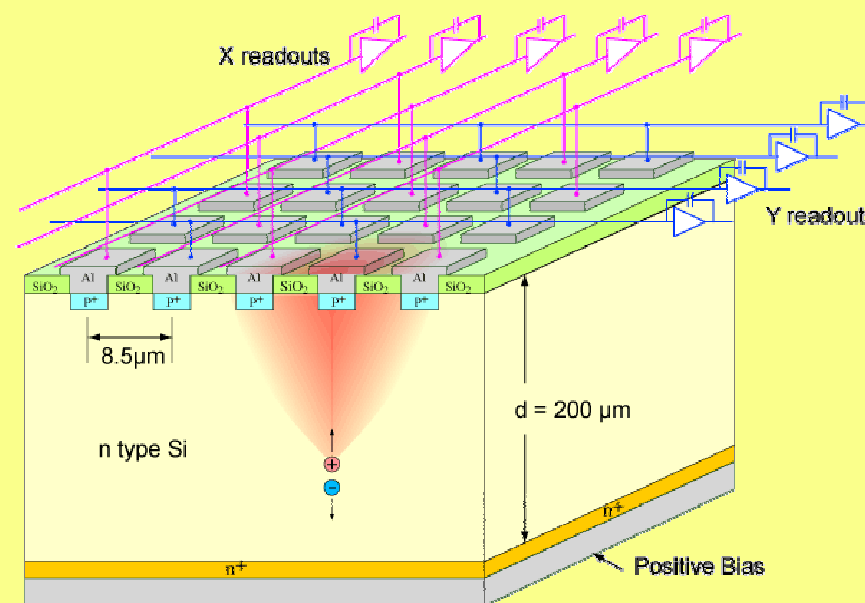
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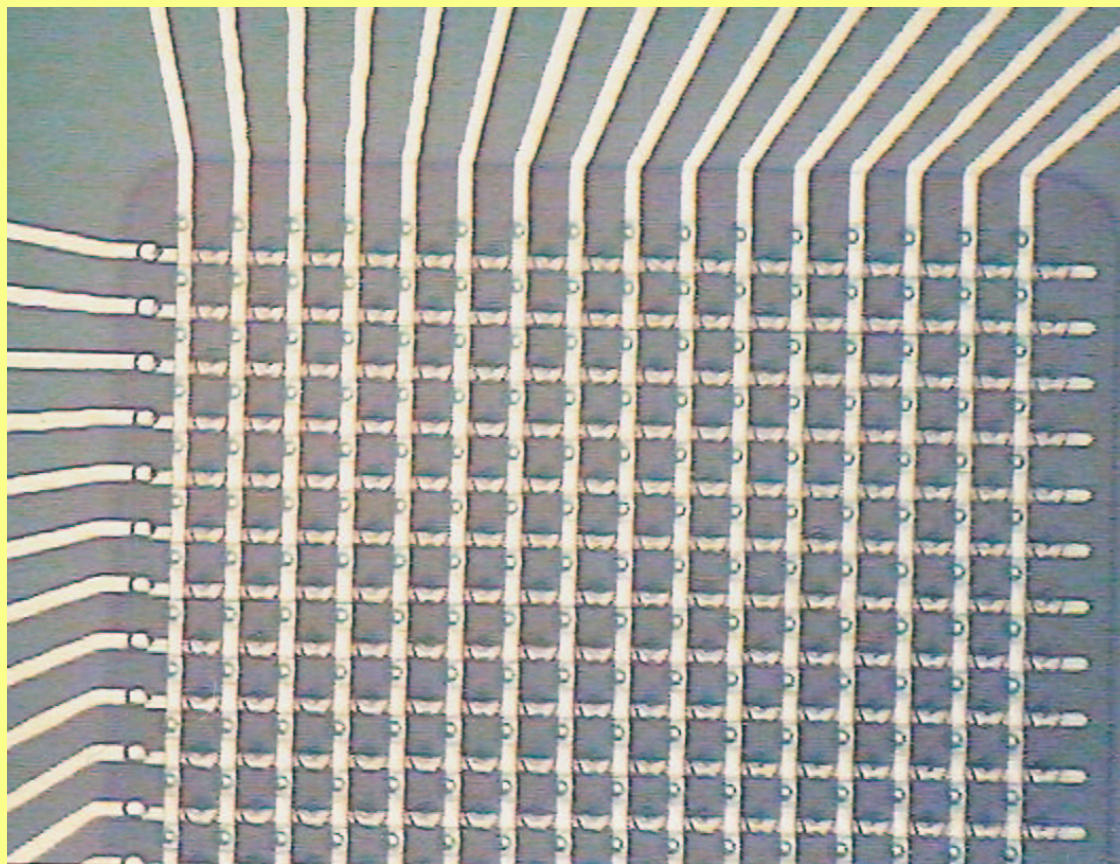
ASD

- Alternating stripixel detectors
 - Pixels are alternately connected to X/Y readout
 - Charge sharing allows the X/Y position to be determined
 - Small pitch allows interpolation to get $<1\mu\text{m}$ resolution



Thanks to: V.Radeka, Z. Li

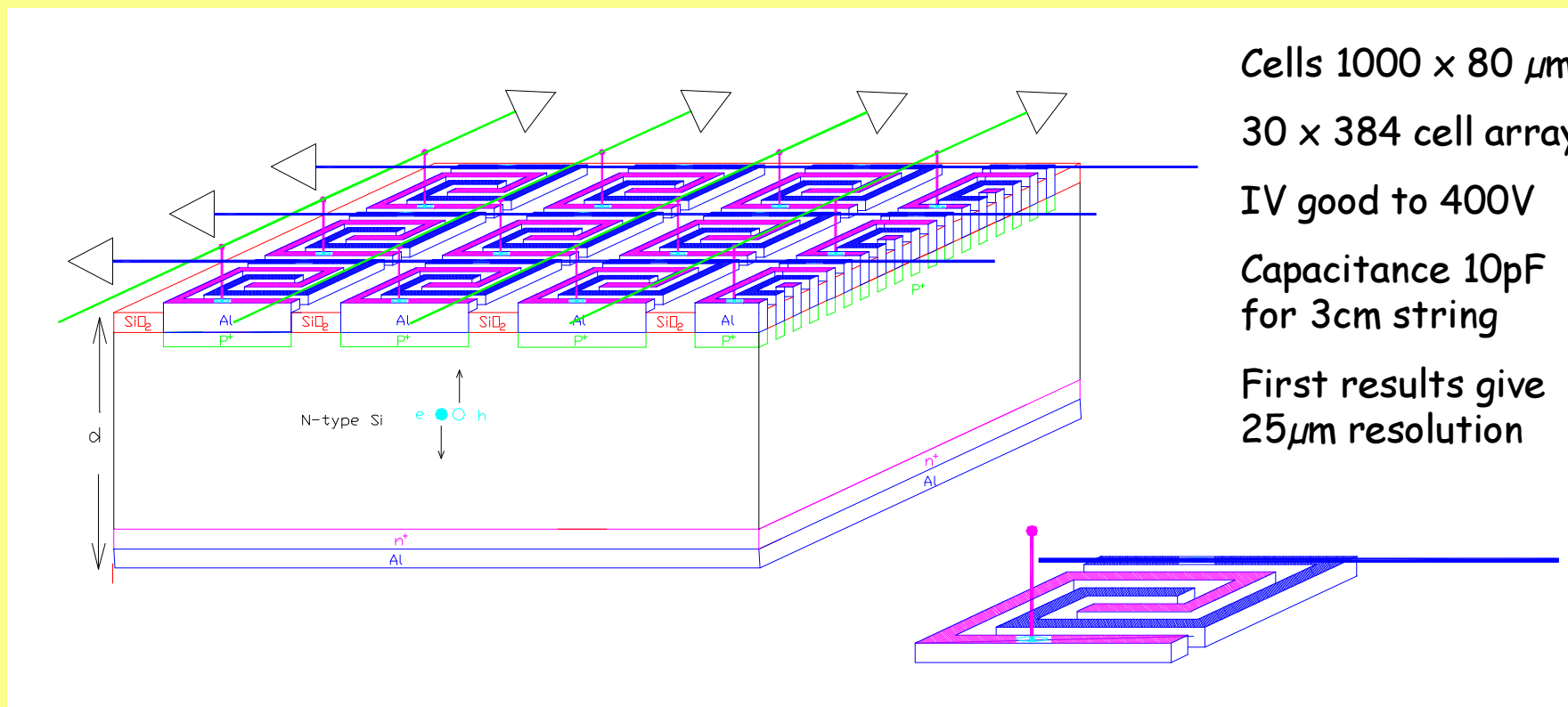
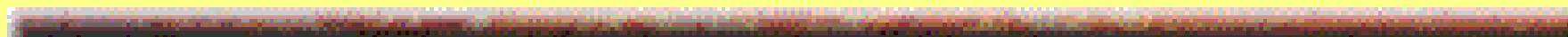
ASD



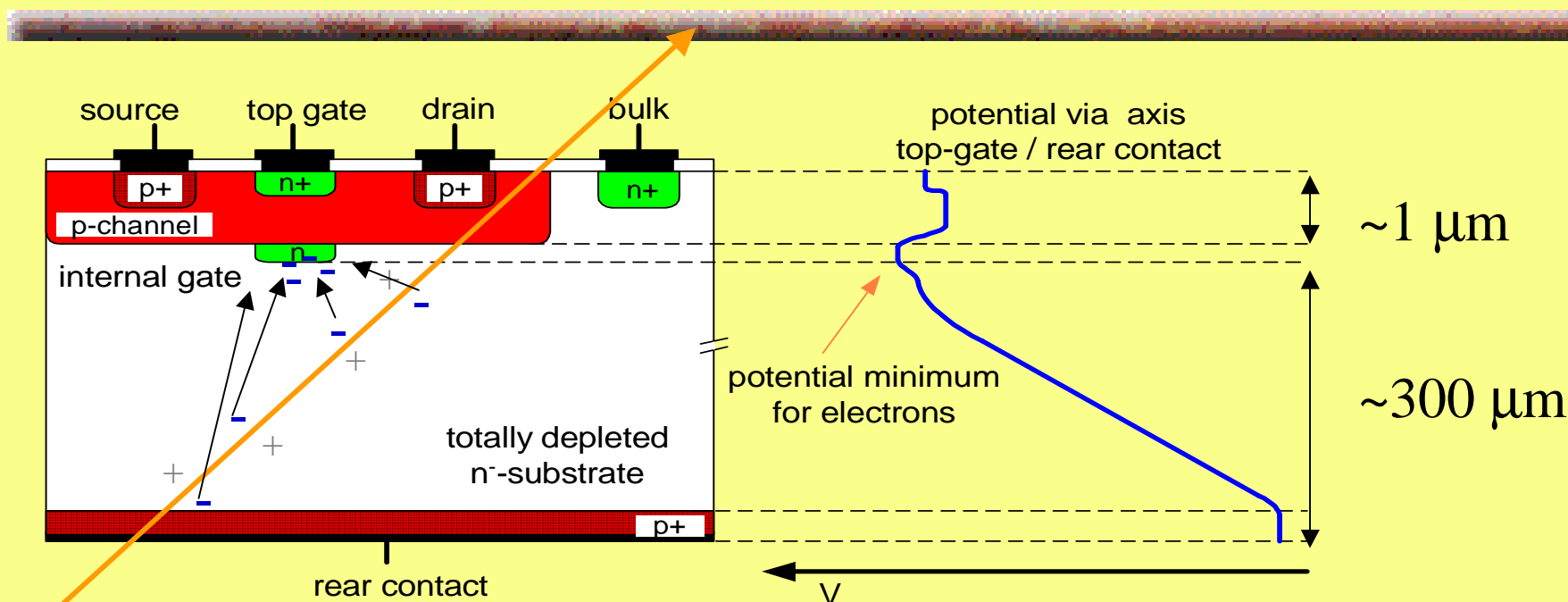
- XY readout with single-sided processing
 - Double metal process
 - $8.5\mu\text{m}$ pitch
 - $2\mu\text{m}$ lines
 - 4×4 mm chip



Interleaved stripixel detector



DEPFET

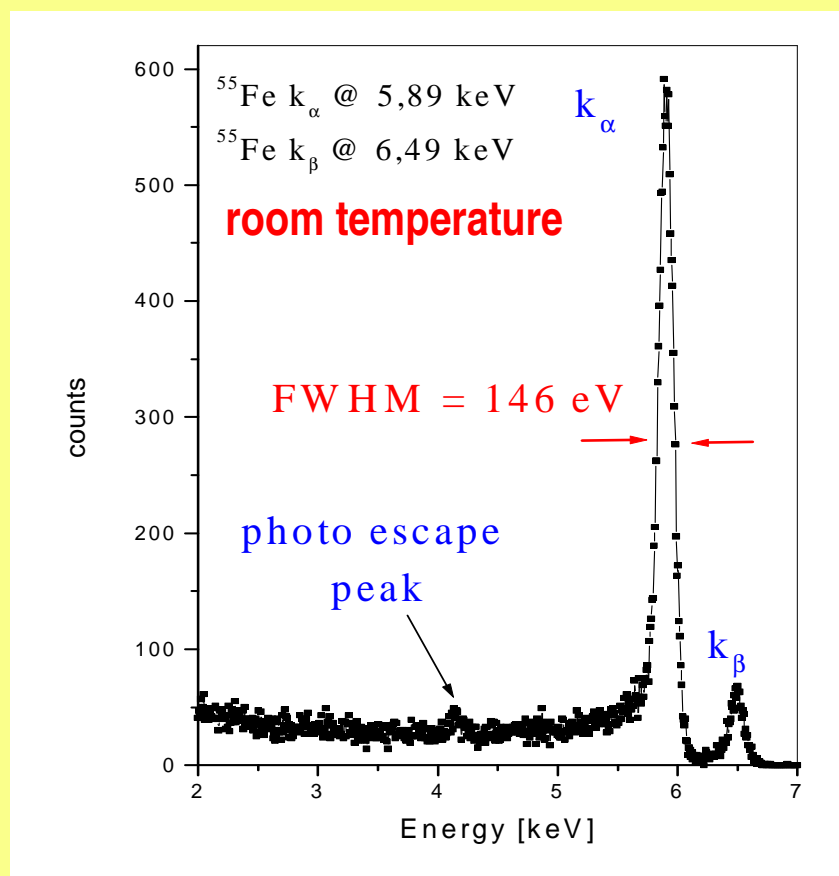


Designed for low noise; first transistor is on the detector
 Substrate is sideways depleted (cf. drift detectors)

J. Kemmer und G. Lutz, NIM A253 (1987) 365



DEPFET resolution

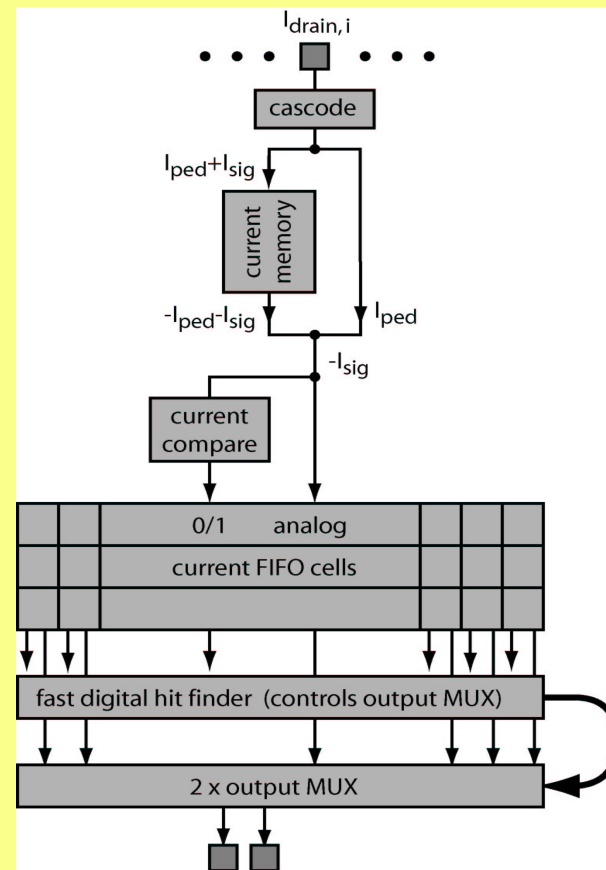


- Noise of single pixel ($50\mu\text{m} \times 50\mu\text{m}$) measured as 4.9 e- at room temperature.
 - Peak resolution limited by Fano factor
 - Matrices made with 69 e- noise at 35 C

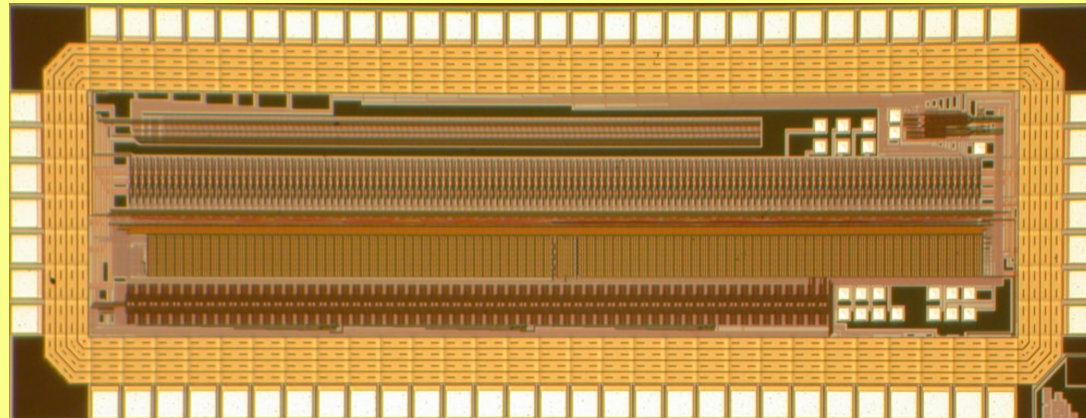


DEPFET: possibilities

- Was proposed for TESLA
 - Signal & pedestal in fast memory cell (20ns)
 - Hit decision with fast comparator
 - Decision and analogue value stored in FIFO
 - Fast digital scanner finds and reads hits; empty FIFO cells are skipped.



Future DEPFET



- Testchip 1.5 x 4 mm contains all basic blocks
 - Designed in rad tolerant 0.25 μ m TSMC
 - Works roughly as advertised



Summary

- Material and geometrical solutions are not exclusive
 - E.g. cold 3d
- Diamond looks mature enough for hybrid pixel detector
- Silicon has a habit of keeping up
- R&D on trapping still rather primitive
- Power will be an increasing problem
- New solutions are still costly, may remain so?